

ABSTRACT

Provided is a double-side coating apparatus which can uniformly coat both surfaces of a substrate to be processed with a coating solution and form uniform coating films on both the surfaces of the substrate to be processed. A double-side coating apparatus (1) includes a holding mechanism (3a) which holds a substrate (2) to be processed so that the thickness direction of the substrate (2) to be processed is a horizontal direction; a rotational driving mechanism which rotates the substrate (2) to be processed in a circumferential direction; a first coating solution nozzle (18a) which jets a coating solution onto one main surface (2a) of the substrate (2) to be processed; and a second coating solution nozzle which jets the coating solution onto the other main surface (2b) of the substrate (2) to be processed. The first coating solution nozzle (18a) and the second coating solution nozzle are symmetrically arranged with respect to a thickness center surface of the substrate (2) to be processed. Provided is an edge rinsing apparatus which can accurately and stably rinse only a fixed width of an outer peripheral portion of the substrate and can easily control the width of the outer peripheral portion to be rinsed even if the width of the outer peripheral portion to be rinsed is small.



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